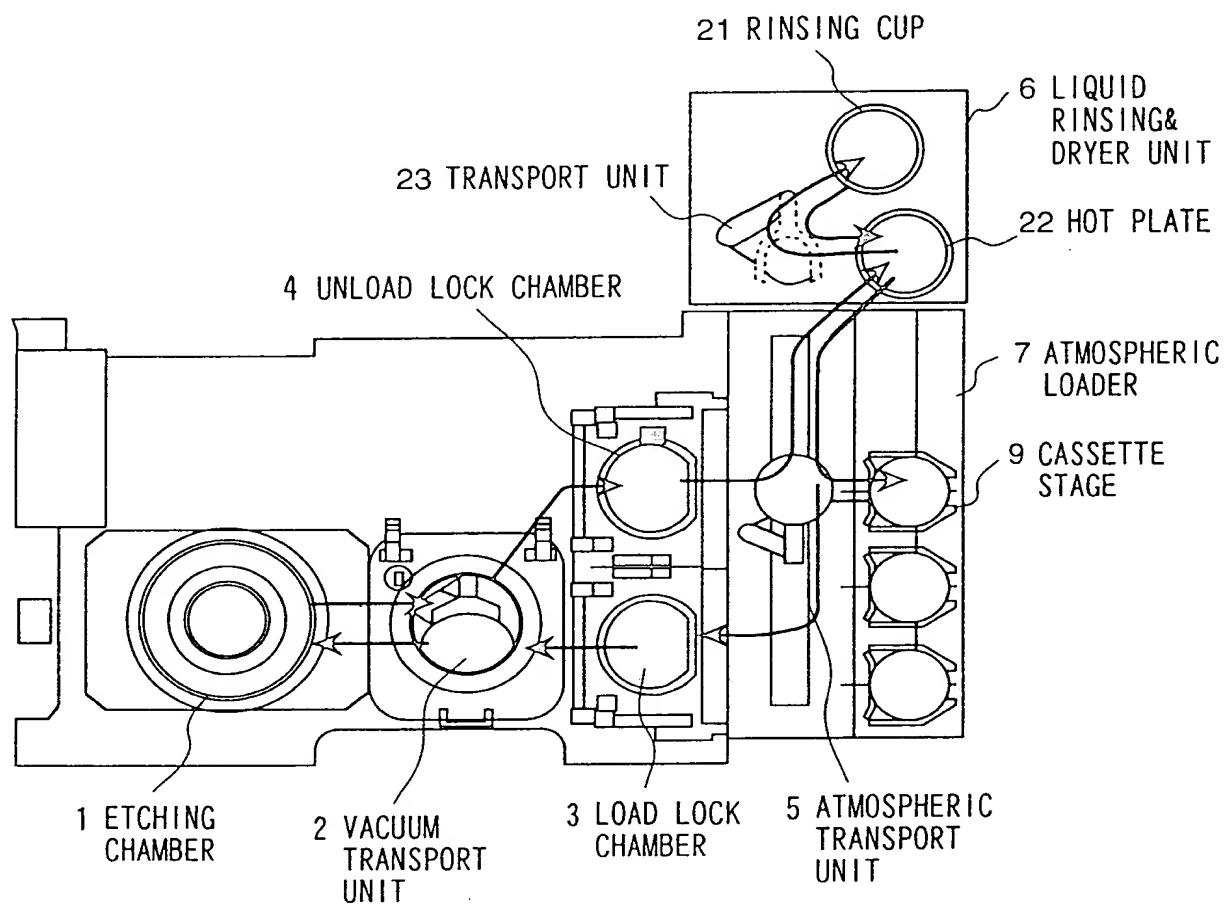




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FIG.1



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FIG.2

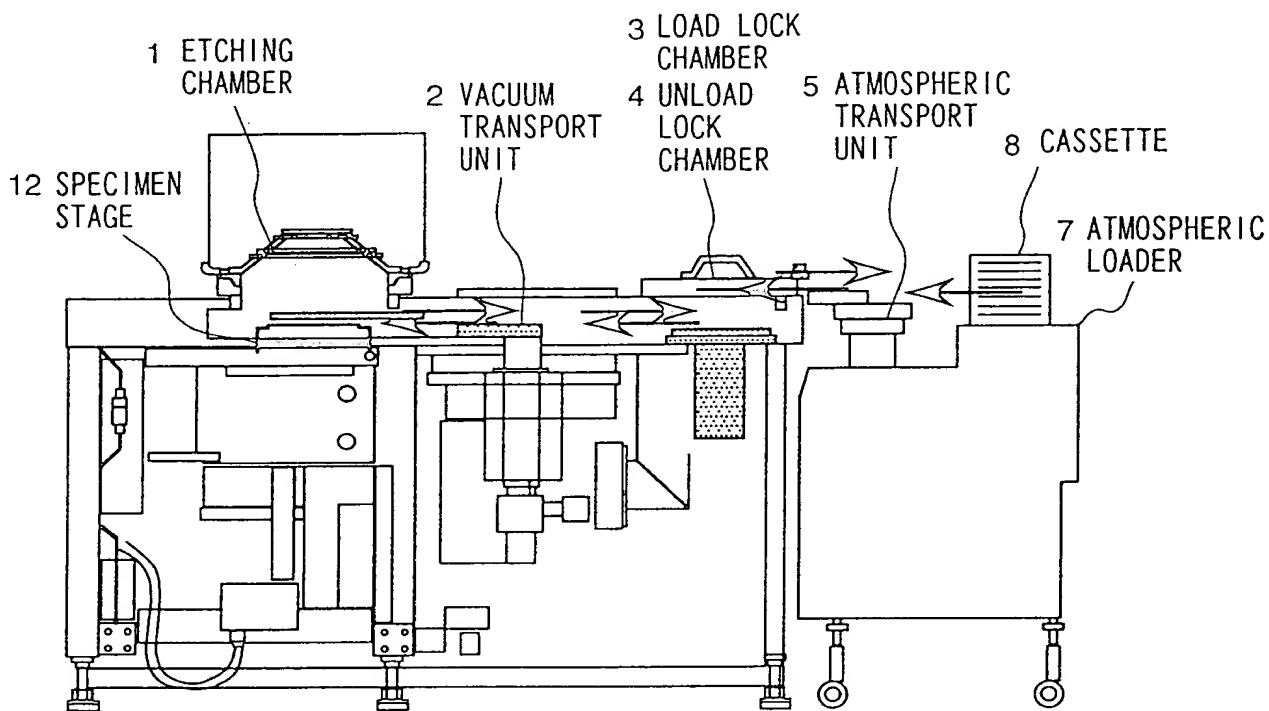
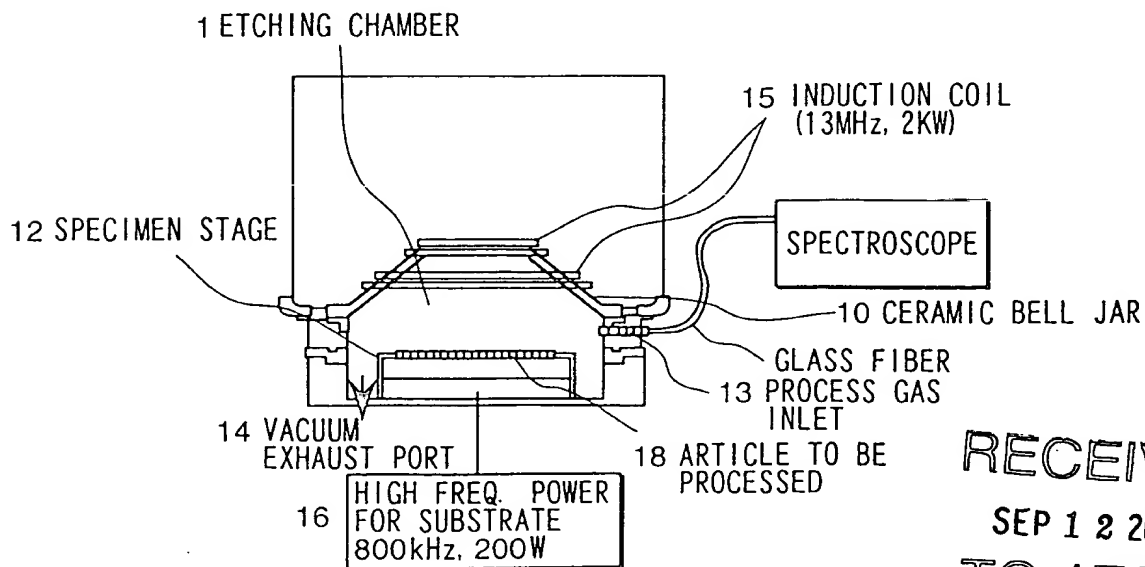


FIG.3



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FIG.4

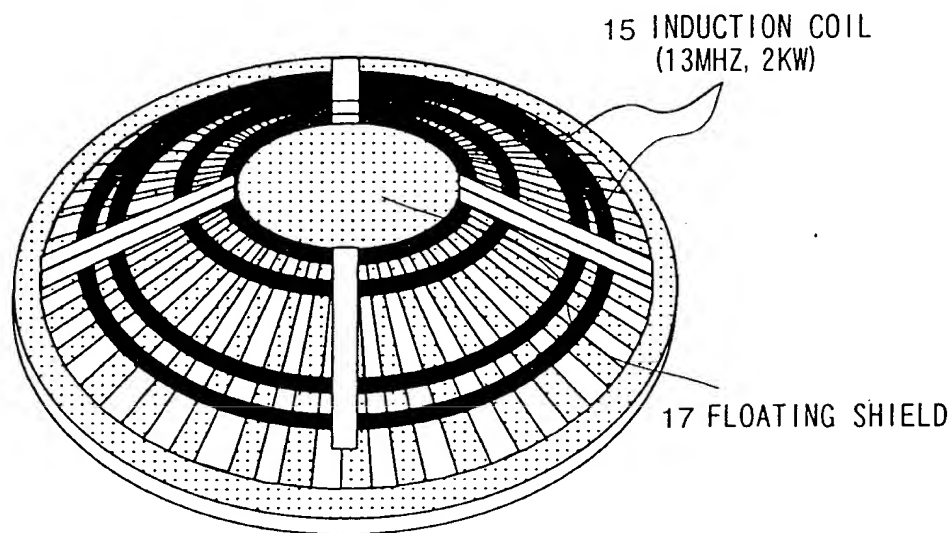
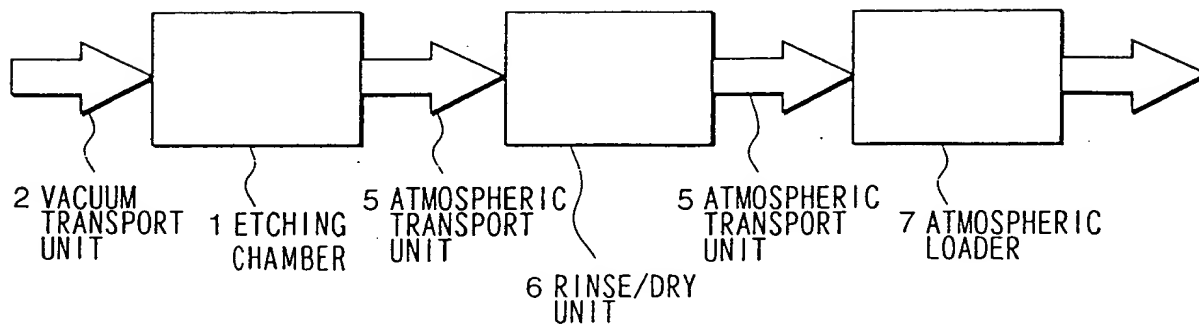


FIG.5



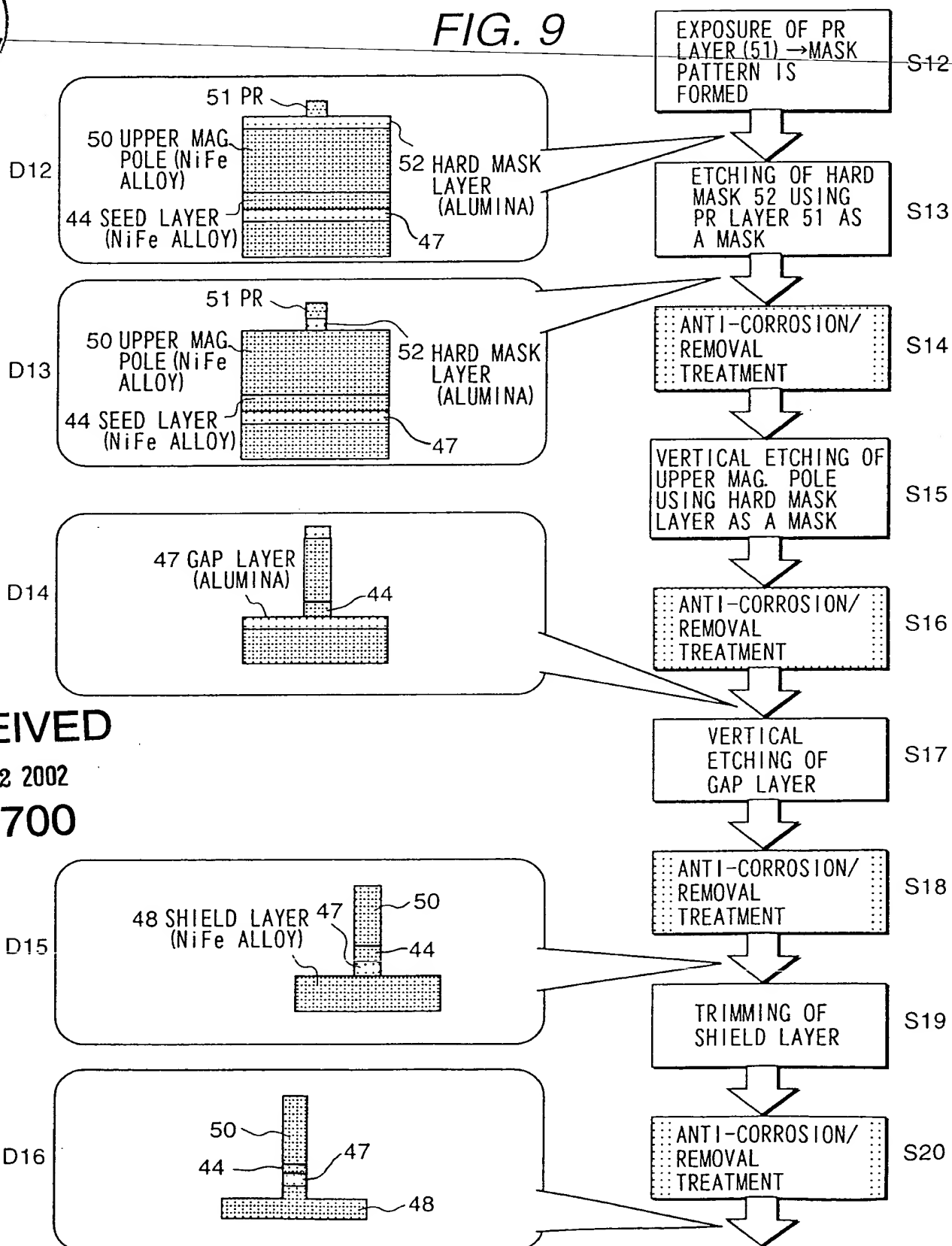
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FIG. 9



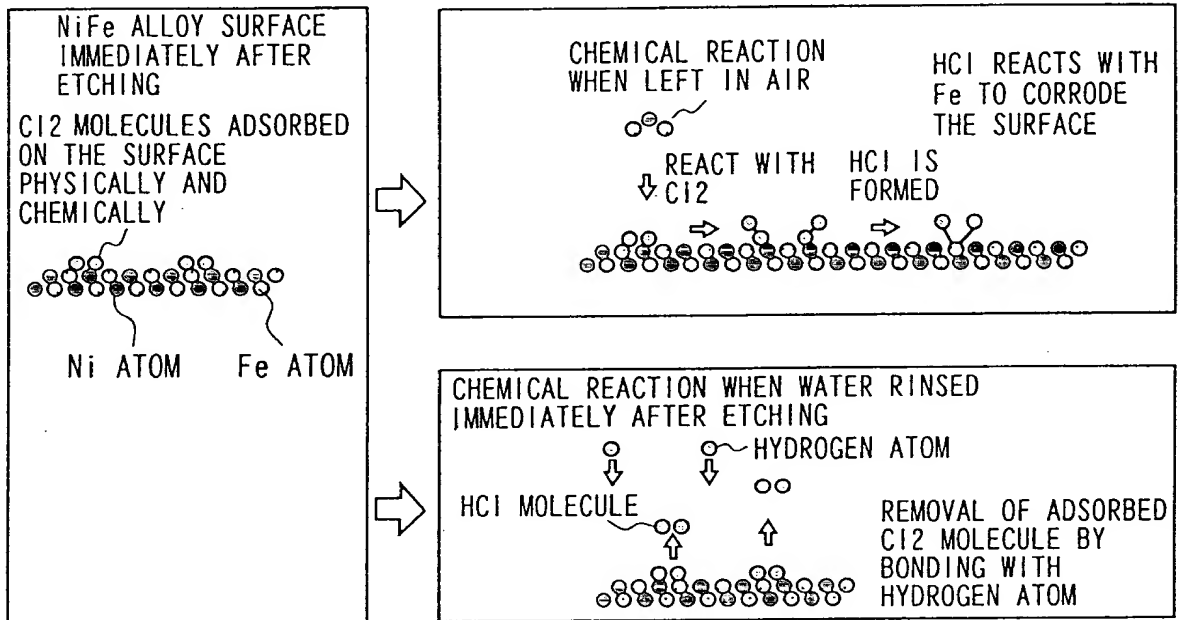
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FIG.10



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FIG.12

| | BEFORE ETCHING | AFTER ETCHING |
|----------------|------------------|---------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|
| PLASMA ETCHING | <p>GAP LAYER</p> | |
| MILLING | | <div style="display: flex; align-items: center;"> <div style="margin-left: 10px;"> <p>A LONGER INITIAL LENGTH OF UPPER MAGNETIC POLE NECESSITATED DUE TO LOW SELECTIVITY RATIO → DIFFICULT TO OBTAIN PRECISE SIZE CONTROL</p> </div> <div style="margin-left: 10px;"> <p>DIFFICULT TO OBTAIN VERTICAL PATTERN</p> </div> </div> |